

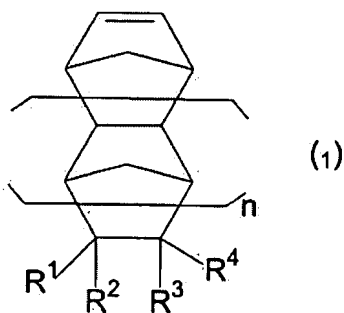
### AMENDMENTS TO THE CLAIMS

1. (Currently amended) A radiation sensitive resin composition which comprises (A) an alicyclic olefin resin soluble in an alkali, (B) an acid-generating agent, (C) a crosslinking agent and (D) a solvent, wherein the alicyclic resin soluble in an alkali is a ring-opening polymer having an acidic group which is obtained by ring-opening polymerization of a polymerizable monomer comprising an alicyclic olefin monomer having an acidic group in a presence of a catalyst comprising ruthenium, followed by hydrogenating an obtained polymer,

wherein the catalyst comprising ruthenium is a catalyst comprising as a main component an organoruthenium compound in which a neutral electron-donating ligand is coordinated.

2. (Original) A radiation sensitive resin composition according to Claim 1, wherein the acidic group is carboxyl group or phenolic hydroxyl group.

3. (Original) A radiation sensitive resin composition according to Claim 1, wherein the alicyclic olefin monomer having an acidic group is an alicyclic olefin monomer represented by following formula (1):



wherein  $R^1$  to  $R^4$  each independently represent hydrogen atom or a group represented by  $-X_m-R'$ , X representing a divalent group, m representing 0 or 1, and  $R'$  representing an alkyl group having 1 to 7 carbon atoms which may have substituents, an aromatic group or an acidic group;

at least one of  $R^1$  to  $R^4$  represents a group represented by  $-X_m-R'$  in which  $R'$  represents an acidic group; and  $n$  represents an integer of 0 to 2.

4. (Canceled)

5. (Currently amended) A radiation sensitive resin composition according to ~~Claim 4~~, Claim 1, wherein the neutral electron-donating ligand is a heterocyclic carbene compound having nitrogen atom.

6. (Original) A radiation sensitive resin composition according to Claim 1, wherein the polymerizable monomer further comprises an alicyclic olefin monomer in which a group having an aromatic group and an aprotic polar group are bonded.

7. (Canceled)

8. (Currently amended) A transparent resin pattern film formed in accordance with a process described in ~~Claim 7~~ Claim 10.

9. (Original) A resin film for electronic parts comprising a resin pattern film described in Claim 8.

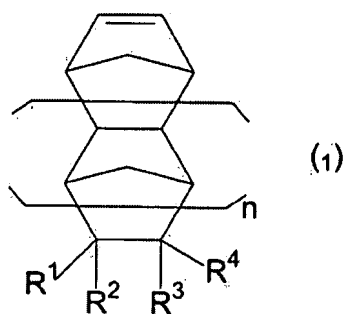
10. (Currently amended) A process for forming a resin pattern film on a substrate which comprises laminating a resin film comprising a radiation sensitive resin composition which comprises (A) an alicyclic olefin resin soluble in an alkali, (B) an acid-generating agent, (C) a crosslinking agent and (D) a solvent, wherein the alicyclic resin soluble in an alkali is a ring-opening polymer having an acidic group which is obtained by ring-opening polymerization of a polymerizable monomer comprising an alicyclic olefin monomer having an acidic group in a presence of a catalyst comprising ruthenium, followed by hydrogenating an obtained polymer to the substrate, irradiating said resin film with an active radiation to form a latent pattern in the

resin film and developing a pattern by bringing the resin film having the latent pattern into contact with a developing solution,

wherein the catalyst comprising ruthenium is a catalyst comprising as a main component an organoruthenium compound in which a neutral electron-donating ligand is coordinated.

11. (Previously presented) A process according to Claim 10, wherein the acidic group is carboxyl group or phenolic hydroxyl group.

12. (Previously presented) A process according to Claim 10, wherein the alicyclic olefin monomer having an acidic group is an alicyclic olefin monomer represented by following formula (1):



wherein  $R^1$  to  $R^4$  each independently represent hydrogen atom or a group represented by  $-X_m-R'$ ,  $X$  representing a divalent group,  $m$  representing 0 or 1, and  $R'$  representing an alkyl group having 1 to 7 carbon atoms which may have substituents, an aromatic group or an acidic group; at least one of  $R^1$  to  $R^4$  represents a group represented by  $-X_m-R'$  in which  $R'$  represents an acidic group; and  $n$  represents an integer of 0 to 2.

13. (Previously presented) A process according to Claim 10, wherein the catalyst comprising ruthenium is a catalyst comprising as a main component an organoruthenium compound in which a neutral electron-donating ligand is coordinated.

14. (Previously presented) A process according to Claim 13, wherein the neutral electron-donating ligand is a heterocyclic carbene compound having nitrogen atom

15. (Previously presented) A process according to Claim 10, wherein the polymerizable monomer further comprises an alicyclic olefin monomer in which a group having an aromatic group and an aprotic polar group are bonded.